

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



Atty.
Dkt. No.

M#

Client Ref.

0306781

P-0381.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: LOF et al.

Appln. No.: 10/705,805

Filing Date: November 12, 2003

Examiner: Unknown

Group Art Unit: 1756

Date: January 6, 2005

Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PA	AR 4,390,273	06/1983	LOEBACH et al.	355	125	
	BR 2004/0109237 A1	06/2004	EPPLÉ et al.			
	CR 6,236,634 B1	05/2001	LEE et al.	369	112	
	DR 2002/0020821 A1	02/2002	VAN SANTEN et al.	250	492	
PA	ER 2004/0119954	06/2004	KAWASHIMA et al.	355	30	
	FR 2004/0125351	07/2004	KRAUTSCHIK	355	53	
	GR					
	HR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclosed	No
PA	IR JP 11-176727	07/1999	JAPAN	SHIRAISHI	X			
	JR JP 2000-058436	02/2000	JAPAN	FUJISHIMA et al.	X			
	KR WO 2004/053950 A1	06/2004	PCT	OWA	X			
	LR WO 2004/053951 A1	06/2004	PCT	MAGOME et al.	X			
	MR WO 2004/053952 A1	06/2004	PCT	MAGOME et al.	X			
	NR WO 2004/053953 A1	06/2004	PCT	NEI et al.	X			
	OR WO 2004/053954 A1	06/2004	PCT	NEI et al.	X			
	PR WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.	X			
	QR WO 2004/053956 A1	06/2004	PCT	NAGASAKA et al.	X			
	RR WO 2004/053957 A1	06/2004	PCT	HIDAKA et al.	X			
	SR WO 2004/053958 A1	06/2004	PCT	MIZUTANI et al.	X			
	TR WO 2004/053959 A1	06/2004	PCT	SHIRAI	X			
	UR WO 2004/053956 A2	06/2004	PCT	GRAUPNER	X			
	VR WO 2004/055803 A1	07/2004	PCT	VAN SANTEN	X		X	
	WR WO 2004/057589 A1	07/2004	PCT	NEIJZEN et al.	X		X	
	XR WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.	X		X	
PA	YR JP 2004-193252	07/2004	Japan	Not Available	X			
	ZR							
	AAR							

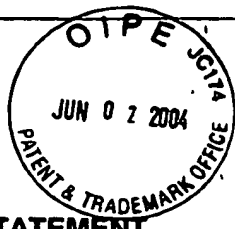
OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

BBR								
CCR								
DDR								
EER								
FFR								

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.



Atty. Dkt. No.	M#	Client Ref.
	306781	P-0381.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: LOF et al.
Appln. No.: 10/705,805
Filing Date: November 12, 2003
Examiner:
Group Art Unit: 1756

Date: June 2, 2004 Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
ML	AR 2004/0075895 A1	04/2004	LIN			
	BR					
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
PL	IR JP 07-132262	05/1995	JAPAN	HIRAKAWA et al.	X				
	JR JP 58-202448	11/1983	JAPAN	KAWAMURA et al.	X				
	KR WO2004/019128	03/2004	PCT	OMURA et al.					
	LR WO 03/077037	09/2003	PCT	ROSTALSKI					
	MR WO 03/077036	09/2003	PCT	SCHUSTER	X				
	NR DD 206 607	02/1984	GERMANY	WESTPHAL et al.			X		
PL	OR DD 221 563	04/1985	GERMANY	PFORR et al.			X		
	PR								
	QR								

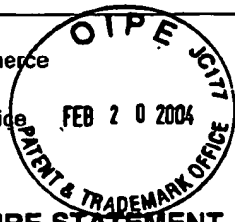
OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

PL	RR	S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51			
	SR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
	TR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004			
	UR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521			
	VR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004			
PL	WR	B. LIN, "The k_3 coefficient in nonparaxial λ/NA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)			
	XR				
	YR				
	ZR				

Examiner *PLT B. H.* Date Considered: 3/18/05

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



Atty. Dkt. No.	M#	Client Ref.
081468	0306781	P-0381.010-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: Joeri LOF et al.

Appln. No.: 10/705,805

Filing Date: November 12, 2003

Date: February 20, 2004

Page

1

of

1

Examiner: Unassigned

Group Art Unit: Unassigned

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
PK	AR 2004/0000627A1	01/01/2004	Karl-Heinz SCHUSTER			
PK	BR 6,600,547	07/29/2003	WATSON et al.			
PK	CR 2004/0021844 A1	02/05/2004	Yutaka SUENAGA			
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					
	NR					

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name		Abstract		Readily Available	
							Enclosed	No	Enclose	No
	OR									
	PR									
	QR									
	RR									
	SR									
	TR									
	UR									
	VR									
	WR									
	XR									

OTHER (Including in this order: Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

PK	YR	H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3			
PK	ZR	S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.			
	AAR				
	BBR				
	CCR				
	DDR				

Examiner

[Signature]

Date Considered: 3/18/05

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.